

Applica

SEARCHED

Class	Sub.	Date	Exmr.
438	689	8/30/02	lh
↓	733	↓	↓
↓	706	↓	↓
↓	691	↓	↓
↓	692	↓	↓

INTERFERENCE SEARCHED

Class	Sub.	Date	Exmr.

SEARCH NOTES (INCLUDING SEARCH STRATEGY)

	Date	Exmr.
WEST Keyword search (dielectric And (TEOS or SiN or silicon) And photoresist And (opening or via or hole) and (anisotropic same etch 13)	8/30/02	lh
WEST Keyword (hard mask, dielectric, opening) (barrier layer, opening, dielectric)	9/4/02	a